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SJ

**INDUSTRY STANDARD OF THE
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**Test methods for measuring surface roughness of polished
monocrystalline silicon carbide wafers**

碳化硅单晶抛光片表面粗糙度的测试方法

(English Translation)

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What this standard covers

This Standard specifies the test silicon carbide single crystal polished surface roughness comprising surface profiler and atomic force microscopy. This Standard applies to silicon carbide single product polished surface roughness testing. Among them, the atomic force microscope method applies only after chemical mechanical polishing or optically polished and the surface roughness of the ups and downs in a few tenths of a micron wide silicon carbide single crystal polished.

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GB/T 14264; GB/T 25915.1-2010